# 点缺陷

#### 空位

1.形成原因: 热量提供了原子克服净吸引力的能量。

2.空位增加了熵指 (entropy),降低了能量。

3.空位平衡浓度: 
$$N_{\nu} = N \exp\left(-\frac{Q_{\nu}}{KT}\right)$$
  $\rightarrow$   $\ln \frac{N_{\nu}}{N} = -\frac{Q_{\nu}}{KT}$  (K=1.38×10<sup>-23</sup>J/atoms·K

或 K= $8.62 \times 10^{-5}$ ev/atoms·K)

4.分类:

A.弗兰克尔空位(Frenkel vacancy): inside-interstitial

陶瓷中: 电中性条件下是阳离子空位+间隙阳离子

离子对数目:  $N_{fr} = N \exp\left(-\frac{Q_{fr}}{2KT}\right)$ 

B.肖脱基空位(Schottky vacancy): inside-surface

陶瓷中: 电中性 (electroneutrality) 条件下是阳离子空位+阴离子空位

平衡浓度:  $N_s = N \exp\left(-\frac{Q_s}{2KT}\right)$ 

### 自间隙原子

1.晶格畸变 (Lattice distortion): 由于原子体积大于间隙位置的空间大小,会导

致周围晶格发生较大畸变。(因此形成概率不大,浓度远低于空位缺陷浓度)

2.能量为空位缺陷能量 3 倍: Qi=3Qv

### 杂质原子

1.分类:取代杂质 (substitutional imurities) 和间隙杂质 (interstitial impurity)

2.金属中的杂质

- 1) 合金(Alloys):人为的添加杂质原子来为材料赋予某种特定性能。( deliberate mixtures of metals)
- 2) 固溶体

#### A.概念

固溶体: When homogeneous mixtures of two or more kinds of atoms occur in the solid state, they are known as *solid solutions*.

溶解度: Solid solutions are made of a host (the solvent or matrix) which dissolves the minor component (solute) The ability to dissolve is called *solubility*.

溶质原子(*Solute*): in an alloy, the element or compound present in lesser amount 溶剂原子(*Solvent*): in an alloy, the element or compound present in greater amount B.分类

<1>置换固溶体:溶质或杂质原子取代或置换溶剂原子。

决定溶质原子在溶剂原子中溶解度的因素

原子尺寸系数(Atomic size factor):atomic radii should be within~15%.

晶体结构 (Crystal structures): 两种晶体金属结构相同。

电负性 ( Electronegativities): 电负性接近。

化合价 (valency): 金属溶剂更易溶解具有较高化合价的溶质原子。

<2>间隙固溶体:杂质原子填充于基质原子的间隙位置。

3.质量百分比(wt%): 
$$C_1 = \frac{m_1}{m_1 + m_2} \times 100$$

4.原子百分比(at%): 
$$C_1 = \frac{n_{m_1}}{n_{m_1} + n_{m_2}} \times 100$$

Weight percent to atomic percent:

Atomic percent to weight percent:

$$C_1' = \frac{C_1 A_2}{C_1 A_2 + C_2 A_1} \times 100$$

$$C_2' = \frac{C_2 A_1}{C_1 A_2 + C_2 A_1} \times 100$$

$$C_1 = \frac{C_1' A_1}{C_1' A_1 + C_2' A_2} \times 100$$

$$C_2 = \frac{C_2' A_2}{C_1' A_1 + C_2' A_2} \times 100$$

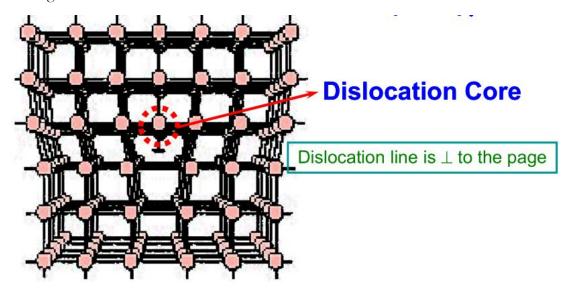
 $C_1 + C_2 = 100$  $C_1' + C_2' = 100$ 

 $C_1 + C_2 = 100$  $C_1' + C_2' = 100$ 

# 线缺陷——位错(Dislocation)

1.位错(②islocation): 是一个线性或一维的缺陷,其周围的原子会产生错排。(形成原因: 局部区域晶体产生错排)

A dislocation is a linear or one-dimensional defect around which some of the atoms are misaligned.

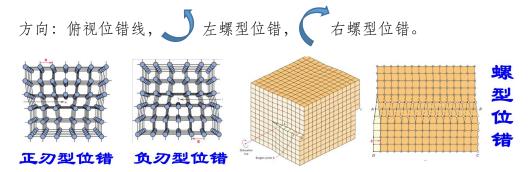


2.分类

**刃型位错 (edge dislocation):** 一个边缘终止于晶体内部的额外原子面,或半原子面。An extra portion of a plane of atoms, or half-plane, the edge of which terminates within the crystal. This is termed an edge dislocation.

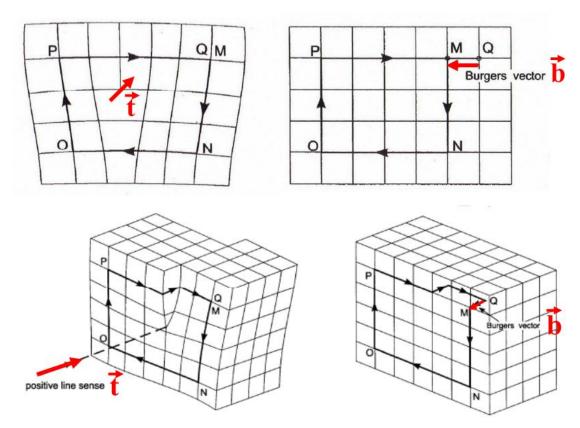
螺型位错 (screw dislocation): 施加的剪切应力使晶格变形。 can be thought of

being formed by shear stress applied to produce the distortion.



3.伯氏矢量 b (BURGERS VECTOR): 表示由位错引起的晶格畸变的大小和方

向。 To describe the magnitude and direction of the main lattice distortion caused by a dislocation we should introduce Burgers vector b.



步骤: 1.定义位错线方向 t

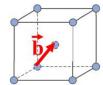
- 2.右手螺旋定则
- 3.标注路径方向
- 4.标注 b 方向——终点指向起点

计算:

BCC:

Notation: 
$$\vec{b} = \frac{1}{2} \langle 111 \rangle$$

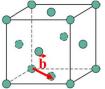
Magnitude: 
$$b = \sqrt{(\frac{a^2}{4} + \frac{a^2}{4} + \frac{a^2}{4})} = \frac{a\sqrt{3}}{2}$$



FCC:

0.000000

Notation:  $\vec{\boldsymbol{b}} = \frac{1}{2} \langle 110 \rangle$ 



Magnitude

$$\mathbf{b} = \sqrt{\left(\frac{a^2}{4} + \frac{a^2}{4} + \frac{0^2}{4}\right)} = \frac{a}{\sqrt{2}}$$

HCP: 
$$\vec{b}(HCP) = \frac{1}{3}\langle 11\overline{2}0\rangle$$

4.位错线:晶体在滑移面上已滑移和未滑移的边界线。

(dislocation motion/slip/glide 位错滑移)

5.位错密度

单位体积内的位错线长度/单位面积内位错线数目。 p=l/vv

6.

# **Geometric Properties of Dislocations**

Dislocation Property	Type of dislocation	
	Edge	Screw
Relation between dislocation line (t) and b	Т	
Slip direction	$\parallel$ to ${f b}$	to <b>b</b>
Direction of dislocation line movement relative to <b>b</b>	Ī	1
Process by which dislocation may leave slip plane	climb	Cross-slip

# 面缺陷

分类

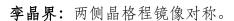
外表面:外表面沿着晶体结构终止的位置。

晶界: 多晶材料中两个具有不同晶粒取向的

小晶粒或晶体之间的界面

晶界角越大,晶界能越大,晶界比晶粒具有 更强化学活性。

**相界:**存在于多相材料中,相界两边具有不同的相。



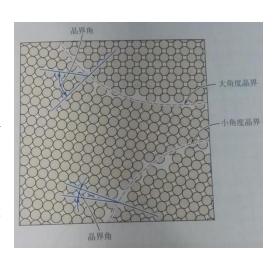
孪晶: 孪晶界间的区域, 由原子位错导致。

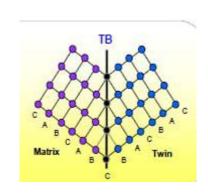
机械孪晶:原子位错产生于机械剪切力。BCC\HCP

退火孪晶:原子位错产生于退火热处理。FCC

堆垛层错: ABCABCABC 堆叠顺序被打乱。

显微技术 (Microscopic techniques): 光学,扫描电子,透射电子 (optical, scanning electron and transmission electron techniques)



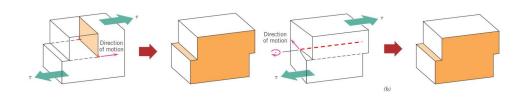


## 变形与强化机制

#### 1.位错运动方向

Edge dislocation line moves parallel to applied stress ( // )

**Screw dislocation** line moves perpendicular to applied stress  $(\bot)$ 



2.位错密度(dislocation density) the total dislocation length per unit volume or the number of dislocations intersecting a unit area.

Carefully solidified metal: 10 3 mm <sup>-2</sup>

Heavily deformed metal:  $10^{9} \sim 10^{10}$  mm  $^{-2}$ 

After heat treating: 10  $^{5}$  ~10  $^{6}$  mm  $^{-2}$ 

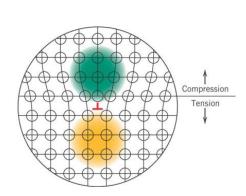
3.位错应变场:金属形变时,约5%的形变能在内部保留,大部分为位错应变能。

**刃型位错**引入压缩,拉伸和剪切晶格应变。

(compressive, tensile, and shear lattice strains)

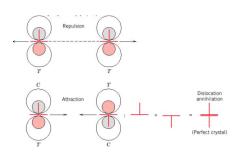
螺型位错只有剪切应变。

应变大小随位错间径像距离增大而降低。



绿:压应力,黄:拉应力

#### 4.位错交互作用:



The strain fields around dislocations cause them to interact(exert force on each other).

When they are in the same plane, they repel if they have the same sign (direction of the Burgers vector) and attract/annihilate if they have opposite signs.

位错周围的应变场导致其交互作用。同性相斥异性相吸。

5.位错倍增(Dislocation multiplication): 塑性变形过程中,位错数量急剧增加。

6.滑移系 (Slip Systems) =滑移面 (slip planes) +滑移方向 (slip directions)

$$FCC=6\times 2=12$$
;  $BCC=4\times 3=12$ ;  $HCP=3\times 1=3$ 

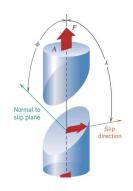
FCC/BCC具有更多的滑移系,由于沿着滑移系可进行大量的塑性变形,因此这些金属塑性更好。

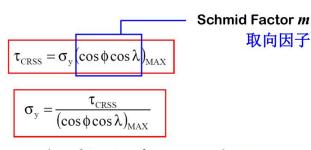
7.分切应力: (resolved shear stress, $au_{R}$  )  $au_{R} = \sigma \cos \phi \cos \lambda$ 

λ: 滑移方向 (红)

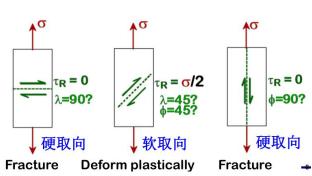
σ: 滑移面法线方向 (绿)

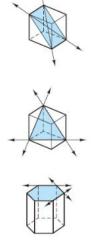
临界分切应力:





Maximum value of  $(\cos\phi \cos\lambda)$  corresponds to  $\phi = \lambda = 45^{\circ} \Rightarrow \cos\phi \cos\lambda = 0.5 \Rightarrow \sigma_{v} = 2\tau_{CRSS}$ 





#### 8.单晶滑移和多晶滑移差异

单晶滑移沿着大量等效且最优的晶面和晶向滑移。

多晶滑移沿着最优取向(最高切应力)方向滑移。

9. 金属强化的三种方式:

#### 细晶强化 (Strengthening by grain-size reduction)

晶界表现出不均匀的晶粒取向。 (GB exhibit discontinuity of grain orientation)

晶界阻碍位错运动。(Grain boundary acts as barrier to dislocation motion.)

大角度晶界更好的阻碍位错运动提高材料强度。

细晶材料比晶粒粗大的材料更有效的阻碍位错运动因为细晶具有更大晶界面积。

Hall-Petch 公式:  $\sigma_v = \sigma_0 + k_v / \sqrt{d}$  d 是晶粒度

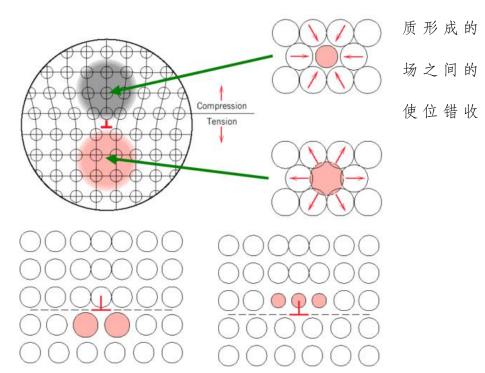
#### 降低延展性提高韧性

#### 细晶强化途径

- 1.加大过冷度
- 2.机械振动/搅拌
- 3.变质处理(孕育处理)

固溶强化(Solid-Solution Strengthening)

位错与杂 晶格 互作用 到阻碍。



钉扎作用: pinning the dislocation

沉淀强化 (Precipitation Strengthening)  $\sigma_y \sim \frac{1}{S}$ 

例: Al 中加入 Li, Li 加入到 lattic 中替换 Al, 密度降低强度增强

### 应变强化/冷变形(Effective Precipitation Strengthening/cold work)

### 回复, 再结晶和晶粒长大

1.回复(去应力退火,扩散退火。)

Heating  $\rightarrow$  increased diffusion  $\rightarrow$  enhanced dislocation motion  $\rightarrow$  decrease in dislocation density by annihilation, formation of low-energy dislocation configurations  $\rightarrow$  relieve of the internal strain energy

加热——增强扩散——增强位错运动——位错密度减少形成低能量位错形态—— —缓解内部应变能

特点: TS, EL%相同

2.再结晶

A.新的无应变,具有低位错密度的等轴晶粒的形成过程,这些晶粒具有冷加工状态之前的特征。

B、The driving force for recrystallization is the difference in internal energy between strained and unstrained material. (驱动力: 应变材料与无应变材料的差异)

C、特点: TS 降低, EL%增加

D.回复和再结晶目的: stress relaxation

E、再结晶程度取决于时间和温度。

F、再结晶温度:熔点的1/3到1/2。再结晶温度随wt%增加而减小。

3.晶粒长大——晶界移动

晶粒长大驱动力: 晶粒尺寸增加, 晶界总体面积减小, 晶界表面能降低。

晶粒尺寸 d 和时间变化关系: 经验关系式

$$d^n - d_o^n = Kt = K_0 t e^{-Q/kT}$$